

Bruce 1 - Tube 1



Facts

Tube 1 is used for the wet oxidation of silicon dioxide.

- Uses hydrogen gas and oxygen to produce a steam for the faster growth of silicon dioxide.
- Wafers are loaded into quartz boats - current sizes include 75mm, 100mm & 150mm.
- Maximum oxide growth is kept to <math><2\mu\text{m}</math>.
- Clean wafers only - no previous metal processing

Other Tubes

- Bruce Tube 1 - Wet Oxide Growth
- Bruce Tube 2 - P type diffusion
- Bruce Tube 3 - N type diffusion
- Bruce Tube 4 - Dry Oxide Growth
- Bruce Tube 5 - External Torch Low Temp Oxide Growth
- Bruce Tube 6 - Wet Oxide Growth
- Bruce Tube 7 - Anneal
- Bruce Tube 8 - High Temp Anneal

Personnel

- Tool Engineer -
- Process Engineer - Sean O'Brien
- Process Engineer - Patricia Meller

Tool & Process Information

- [Bruce Furnace Recipe Request Sheet](#)
 - If a new recipe is needed for the Bruce Furnace, fill out this sheet and return to Sean O'Brien

Manuals & Users

- [Bruce Furnace Manual](#)
- [Bruce Furnace Certification Checklist](#)